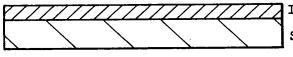


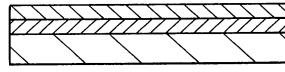
Fig.1A



INSULATING FILM
SUBSTRATE

RESIST COATING/PRE-BAKING

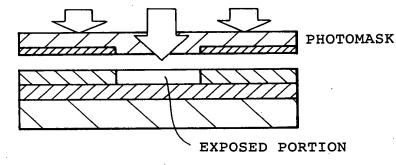
Fig.1B



RESIST
(IN THE CASE OF
A POSITIVE
RESIST)

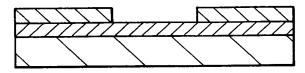
MASK ALIGNMENT/EXPOSURE

Fig.1C



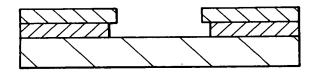
## RESIST DEVELOPMENT/POST-BAKING

Fig.1D



## INSULATING FILM ETCHING

Fig.1E



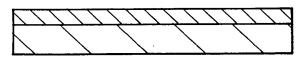
## RESIST ASHING

Fig.1F



## POLYSILAZANE COATING

Fig.2A



POLYSILAZANE

MASK ALIGNMENT/EXPOSURE

Fig.2B

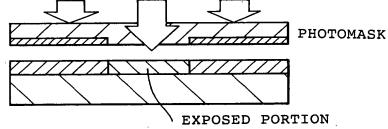


Fig.2C

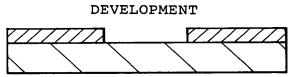


Fig.2D

